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## Patent Abstracts of Japan

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APPLICANT : MITSUBISHI METAL CORP;

INVENTOR : MARUYAMA HITOSHI;

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TITLE : MANUFACTURE OF TARGET FOR TITANIUM SILICIDE SPUTTERING

ABSTRACT : PURPOSE: To manufacture a good target having less segregation of its structure and oxygen contents at the time of manufacturing said target by melting Ti and Si in a nonoxidizing atmosphere into alloy, thereafter grinding it and subjecting said powder to hot pressing.

CONSTITUTION: Pure Si powder, 38.7wt.%, and 61.3wt.% Ti plate are jointly charged to a water-cooling Cu hearth; vacuum drawing is executed thereto and the Si powder and Ti plate are melted to cast Ti-Si alloy. The ingot of said Ti-Si alloy is ground and sieved, by which the target of titanium silicide is manufactured by hot pressing with that having 50-500µm average grain size. The target of titanium silicide having less segregation of components and oxygen contents inside of the target and further having excellent strength can be obtd.

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